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Wrinkling of a stiff thin film bonded to a pre-strained, compliant substrate with finite thickness

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A stiff thin film bonded to a pre-strained, compliant substrate wrinkles into a sinusoidal form upon release of the pre-strain. Many analytical models developed for the critical pre-strain for wrinkling assume that the substrate is semi-infinite. This critical pre-strain is actually much smaller than that for a substrate with finite thickness (Ma Y *et al.* 2016 *Adv. Funct. Mater.* (doi:10.1002/adfm.201600713)). An analytical solution of the critical pre-strain for a system of a stiff film bonded to a pre-strained, finite-thickness, compliant substrate is obtained, and it agrees well with the finite-element analysis. The finite-thickness effect is significant when the substrate tensile stiffness cannot overwhelm the film tensile stiffness.

1. Introduction

A stiff film bonded to a pre-strained, compliant substrate wrinkles upon releasing the pre-strain [1,2]. Such a system has many important applications in stretchable

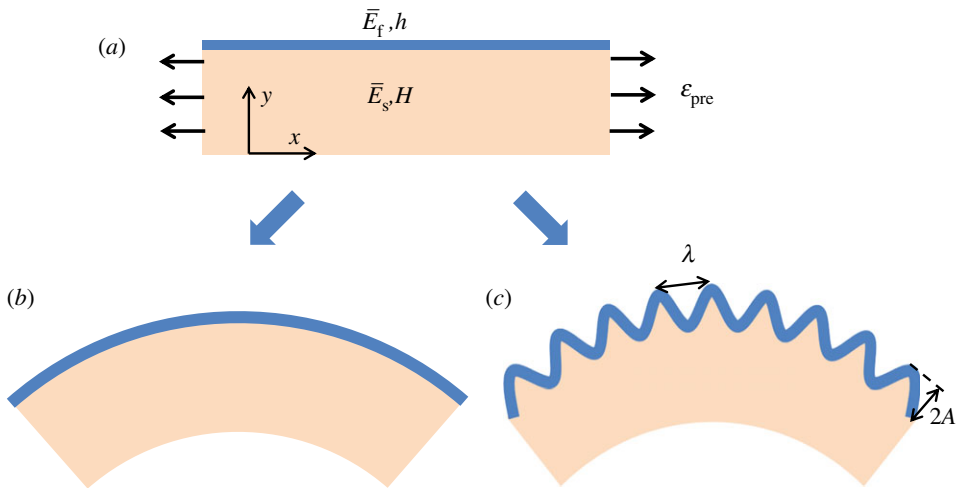


Figure 1. Schematic illustrations. (a) A stiff thin film bonded to a pre-strained, compliant substrate with finite thickness; (b) bending of the film/substrate system upon release of the small pre-strain; and (c) wrinkling of the stiff thin film, along with bending of the film/substrate system, upon release of large pre-strain. (Online version in colour.)

inorganic electronics [3–8], micro/nano pattern formation [9–11], high-precision micro/nano measurement techniques [12], tuneable metamaterials [13], nanocomposites [14], stretchable transistors [15] and biomimetic materials [16]. Analytical models have been developed for wrinkling of a stiff thin film on a pre-strained compliant substrate [17–21]. The results identify the critical pre-strain for wrinkling, below which the film remains flat. However, all of these studies assume that the substrate is semi-infinite such that its tensile stiffness overwhelms that of the film. Consequently, the substrate recovers the initial length after the pre-strain is released and its bottom remains flat.¹

The critical pre-strain for wrinkling obtained for a semi-infinite substrate, however, is smaller than the numerical and experimental results for a substrate with finite thickness [22], even for substrates that are more than 1000 times thicker than the film. This is because the substrate elastic modulus E_s is often more than five orders of magnitude smaller than the film elastic modulus E_f [1,2], such that the substrate tensile stiffness $E_s H$ cannot overwhelm the film tensile stiffness $E_f h$, where H and h are the substrate and film thicknesses, respectively (figure 1a). Consequently,

- (1) the substrate cannot shrink back to its initial length after release of the pre-strain; and
- (2) the film/substrate system may bend after the pre-strain is released (figure 1b).

The recent study by Ma *et al.* [22] accounted for (1), while this paper aims to establish an analytic model for both (1) and (2). The resulting critical pre-strain will be useful for many applications such as the strain-limiting design of materials [22] and tuneable optical design of the intensity for diffraction peaks [23].

2. Analytical model

A stiff thin film is bonded onto a pre-strained (ϵ_{pre}), compliant substrate (figure 1a). For small pre-strain, the stiff film does not wrinkle upon release of the pre-strain; instead, the film and substrate bend (figure 1b). Let ϵ denote the membrane strain in the film. The strain in the substrate

¹Huang *et al.* [24] studied the finite thickness of a substrate subjected to compression, to be discussed below.

is $\varepsilon_s(y) = \varepsilon_{\text{pre}} + \varepsilon - \kappa(H - y)$, where κ is the curvature of the substrate, and the co-ordinate y is shown in figure 1a. The potential energy is

$$U_{\text{bend}} = \frac{1}{2} \bar{E}_f h \varepsilon^2 + \frac{1}{2} \bar{E}_s \int_0^H [\varepsilon_{\text{pre}} + \varepsilon - \kappa(H - y)]^2 dy, \quad (2.1)$$

where $\bar{E}_f = E_f/(1 - \nu_f^2)$ and $\bar{E}_s = E_s/(1 - \nu_s^2)$ are the plane-strain moduli of the stiff thin film and compliant substrate, respectively, and ν_f and ν_s are the Poisson's ratios.

Minimization of the potential energy $\partial U_{\text{bend}}/\partial \varepsilon = 0$ and $\partial U_{\text{bend}}/\partial \kappa = 0$ gives $\varepsilon = -\bar{E}_s H \varepsilon_{\text{pre}} / (4\bar{E}_f h + \bar{E}_s H)$ and $\kappa = -6\bar{E}_f h \varepsilon_{\text{pre}} / [H(4\bar{E}_f h + \bar{E}_s H)]$. Equation (2.1) then becomes

$$U_{\text{bend}} = \frac{\bar{E}_f h \bar{E}_s H \varepsilon_{\text{pre}}^2}{2(4\bar{E}_f h + \bar{E}_s H)}. \quad (2.2)$$

Once the pre-strain exceeds the critical pre-strain (to be determined), the stiff film wrinkles on the top surface of the substrate (figure 1c) and the film/substrate bends. In addition to the membrane strain ε , the film is also subjected to wrinkling with amplitude A and period λ to be determined. The strain energy in the film is [24]

$$U_{\text{film}} = \frac{1}{2} \bar{E}_f h \varepsilon^2 - \frac{1}{4} \bar{E}_f h |\varepsilon| k^2 A^2 + \frac{1}{32} \bar{E}_f h k^4 A^4 + \frac{1}{48} \bar{E}_f h^3 k^4 A^2, \quad (2.3)$$

which degenerates to the first term on the right-hand side of equation (2.1) when the amplitude $A = 0$; here $k = 2\pi/\lambda$. The strain energy in the substrate is

$$U_{\text{substrate}} = \frac{1}{2} \bar{E}_s \int_0^H [\varepsilon_{\text{pre}} + \varepsilon - \kappa(H - y)]^2 dy + \frac{\bar{E}_s}{4} k A^2 g(kH), \quad (2.4)$$

which degenerates to the last term in equation (2.1) when the amplitude $A = 0$. The last term in the above equation is the strain energy in the substrate due to wrinkling [24], and the function g is

$$g(x) = \frac{\cosh(2x) + 1 + 2x^2}{2 \sinh(2x) - 4x}, \quad (2.5)$$

for an incompressible substrate ($\nu_s = 0.5$), and g approaches $1/2$ for a semi-infinite substrate. The potential energy is the sum of U_{film} and $U_{\text{substrate}}$,

$$U_{\text{bend+wrinkle}} = \frac{1}{2} \bar{E}_f h \varepsilon^2 + \frac{1}{2} \bar{E}_s \int_0^H [\varepsilon_{\text{pre}} + \varepsilon - \kappa(H - y)]^2 dy + \frac{1}{4} \bar{E}_f h (f - |\varepsilon|) k^2 A^2 + \frac{1}{32} \bar{E}_f h k^4 A^4, \quad (2.6)$$

where

$$f = \frac{k^2 h^2}{12} + \frac{\bar{E}_s g(kH)}{kh \bar{E}_f}. \quad (2.7)$$

Minimization of the potential energy with respect to k and A , $\partial U_{\text{bend+wrinkle}}/\partial k = 0$ and $\partial U_{\text{bend+wrinkle}}/\partial A = 0$, gives

$$6 \frac{g(kH) - g'(kH)kH}{(kH)^3} = \frac{\bar{E}_f h^3}{\bar{E}_s H^3} \quad (2.8)$$

and

$$k^2 A^2 = 4(|\varepsilon| - f), \quad (2.9)$$

where $g'(x) = dg(x)/dx$. Equation (2.8) suggests that the normalized period, $\lambda/[(\bar{E}_f/\bar{E}_s)^{1/3}h]$, or equivalently $kh/(\bar{E}_s/\bar{E}_f)^{1/3}$, depends only on the film/substrate bending stiffness ratio $\bar{E}_f h^3/\bar{E}_s H^3$, as shown in figure 2. The period becomes independent of the substrate thickness H when the bending stiffness ratio $\bar{E}_f h^3/\bar{E}_s H^3$ is less than 0.01, which is consistent with Huang *et al.* [24].

Minimization of the potential energy with respect to ε and κ , $\partial U_{\text{bend+wrinkle}}/\partial \varepsilon = 0$ and $\partial U_{\text{bend+wrinkle}}/\partial \kappa = 0$, gives $\varepsilon = 4\bar{E}_f h f / (\bar{E}_s H) - \varepsilon_{\text{pre}}$, and $\kappa = 6\bar{E}_f h f / (\bar{E}_s H^2)$, where f is obtained

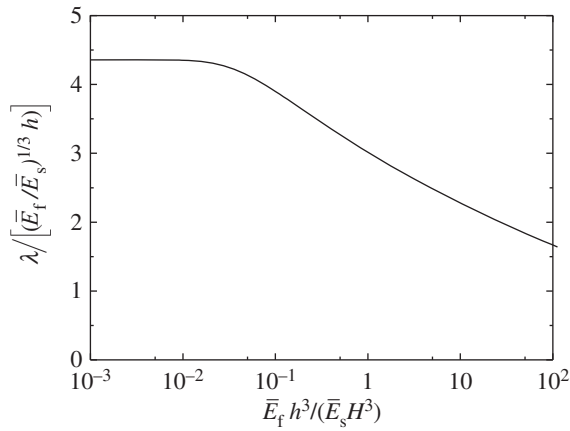


Figure 2. The normalized wrinkle period $\lambda / [(\bar{E}_f / \bar{E}_s)^{1/3} h]$ versus the film-to-substrate bending stiffness ratio $[\bar{E}_f h^3 / (\bar{E}_s H^3)]$.

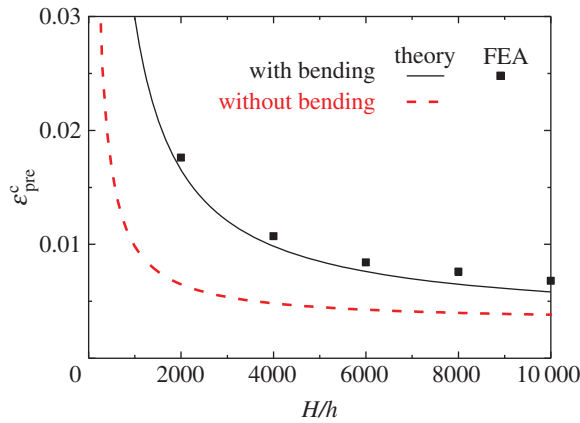


Figure 3. The critical pre-strain ε_{pre}^c versus the substrate-to-film thickness ratio (H/h) for a polyimide film on a PDMS substrate. FEA, finite-element analysis; PDMS, polydimethylsiloxane. (Online version in colour.)

from equation (2.7). The potential energy then becomes

$$U_{\text{bend+wrinkle}} = \bar{E}_f h f \left[\varepsilon_{\text{pre}} - \frac{1}{2} \left(\frac{4\bar{E}_f h}{\bar{E}_s H} + 1 \right) f \right]. \quad (2.10)$$

Comparison of the potential energy in equations (2.2) and (2.10) suggests that wrinkling occurs when $U_{\text{bend}} > U_{\text{bend+wrinkle}}$, which gives

$$\varepsilon_{\text{pre}} > \left(\frac{4\bar{E}_f h}{\bar{E}_s H} + 1 \right) f = \left(\frac{4\bar{E}_f h}{\bar{E}_s H} + 1 \right) \left[\frac{k^2 h^2}{12} + \frac{\bar{E}_s g(kH)}{kh\bar{E}_f} \right], \quad (2.11)$$

where k, f and g are obtained from equations (2.5), (2.7) and (2.8), respectively. It should be pointed out that equation (2.11) also ensures that the right-hand side of equation (2.9) is positive such that there is a solution for the amplitude A .

3. Discussion

When the bending stiffness of the substrate overwhelms that of the film, i.e. $\bar{E}_f h^3 / (\bar{E}_s H^3) < \sim 0.01$, equation (2.11) can be further simplified as

$$\varepsilon_{\text{pre}} > \varepsilon_{\text{pre}}^c = \frac{1}{4} \left(\frac{4\bar{E}_f h}{\bar{E}_s H} + 1 \right) \left(\frac{3\bar{E}_s}{\bar{E}_f} \right)^{2/3}. \quad (3.1)$$

For $H \rightarrow \infty$, the above equation degenerates to that for a semi-infinite substrate [1,2]. The critical pre-strain $\varepsilon_{\text{pre}}^c$ in equation (3.1) is larger than $\frac{1}{4}((\bar{E}_f h / \bar{E}_s H) + 1)(3\bar{E}_s / \bar{E}_f)^{2/3}$ [22], which neglects the effect of film/substrate bending. Figure 3 shows the critical pre-strain $\varepsilon_{\text{pre}}^c$ versus the thickness ratio H/h for a polyimide film ($E_f = 2.5$ GPa, $\nu_f = 0.34$) on a polydimethylsiloxane substrate ($E_s = 1$ MPa, $\nu_s = 0.5$). The results obtained from finite-element analysis agree well with the critical pre-strain in equation (3.1).

Competing interests. We declare we have no competing interests.

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